

## AMENDMENT TRANSMITTAL LETTER

Docket No.  
M4065,0353/P353-A

DEC 26 2002

Application No.  
09/982,954Filing Date  
October 22, 2001Examiner  
Karla MooreArt Unit  
1763

Applicant(s): Gurtej Sandhu, et al.

Invention: ATOMIC LAYER DOPING APPARATUS AND METHOD

## TO THE COMMISSIONER FOR PATENTS

Transmitted herewith is an amendment in the above-identified application.

The fee has been calculated and is transmitted as shown below.

CLAIMS AS AMENDED					
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate	
Total Claims	19	- 20 =		x	0.00
Independent Claims	3	- 3 =		x	0.00
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					
Other fee (please specify):					
<b>TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:</b>					0.00

 Large Entity Small Entity No additional fee is required for this amendment. Please charge Deposit Account No. \_\_\_\_\_ in the amount of \$ \_\_\_\_\_. A duplicate copy of this sheet is enclosed. A check in the amount of \$ \_\_\_\_\_ to cover the filing fee is enclosed. Payment by credit card. Form PTO-2038 is attached. The Commissioner is hereby authorized to charge and credit Deposit Account No. 04-1073 as described below. A duplicate copy of this sheet is enclosed. Credit any overpayment. Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.

Dated: December 26, 2002

Thomas J. D'Amico

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:  
Gurtej Sandhu et al.,

Application No.: 09/982,954

Group Art Unit: 1763

Filed: October 22, 2001

Examiner: Karla Moore

For: ATOMIC LAYER DOPING APPARATUS  
AND METHOD

HIS  
12/31/02  
MW

AMENDMENT

Commissioner for Patents  
Washington, DC 20231

Dear Sir:

Responsive to the Office Action of September 26, 2002, rejecting claims 1-17,  
please amend the above-identified U.S. patent application as follows:

In the Claims:

Please add new claims 46 and 47.

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46. (new) An atomic layer doping apparatus comprising:

B1  
a first atomic layer doping region for depositing a first dopant species on a  
first substrate as a monolayer;

a second atomic layer doping region for diffusing said first dopant species in  
said first substrate, said first and second doping regions being chemically isolated from one  
another by an inert gas curtain, wherein said inert gas curtain is provided at a higher  
pressure than said first dopant species; and,